

Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.
M122-1427SERIAL NO.
09/559,903LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)

JAN 23 2002

APPLICANT
Zhiping Yin et al.FILING DATE
April 26, 2000GROUP
2815

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
92	AA	0 942 330 A1	9/99	EPO	—	—		
91	AB	09-050993/JP9750993	2/97	Japan	—	—		
91	AC	406244172/6-244172	9/94	Japan	—	—		
91	AD	593,727	10/47	GB	—	—		
91	AE	5-263255/JP5263255	10/93	Japan	—	—		
91	AF	0 464 515 A3	1/92	EPO	—	—		
91	AG	0 771 886 A1	5/97	EPO	—	—		
91	AH	63-157443/JP63157443 A	6/88	JP	—	—		

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

94	AI	Robert Withnall et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", 1988 American Chemical Society, pp 594-602
94	AJ	Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.
94	AK	Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.
94	AL	Joubert, O. et al., "Application of Plasma Polymerized Methylsilane in an All Dry Resist Process for 193 and 248nm Lithography", Microelectronic Engineering 30 (1996), pp. 275-278.
94	AM	Ajeay M. Joshi et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV Photolithography", SPIE Vol 1925/709, pp. 709-720
94	AN	M. Matsuura et al., "A Highly Reliable Self-planarizing Low-k Intermetal Dielectric for Sub-quarter Micron Interconnects", IEEE 7/97 pp 31.6.1-31.6.4
94	AO	O. Horie et al., "Kinetics and Mechanism of the Reactions of O(P) with SiH ₄ , CH ₃ SiH ₃ , (CH ₃) ₂ SiH ₂ and (CH ₃) ₃ SiH", 1991 American Chemical Society, pp 4393-4400
94	AP	McClatchie, S. et al., "Low Dielectric Constant Flowfill Technology for IMD Applications", Proceed. of 3d Internatl. Dielectrics for ULSI Multilevel Interconnection Conf, Santa Clara, CA, Feb. 1997, pp. 34-40.
94	AQ	Beckman, K. et al., "Sub-Micron Gap Fill and In-Situ Planarisation Using Flowfill™ Technology", ULSI Conf, Portland, OR, Oct. 1995, pp. 1-7.
94	AR	Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-
94	AS	IBM Technical Disclosure Bulletin "Low-Temperature Deposition of SiO ₂ , Si ₃ N ₄ or SiO ₂ -Si ₃ N ₄ ," Vol. 28, No. 9, p. 4170, Feb.
94	AT	TEXT: Ralls, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.
94	AU	ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes", Electrochemical Society Meeting Abstract No. 358, 191 st Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.
94	AV	Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from www.semiconductor-intl.com).
94	A	Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.
94	AX	Julius Grant, "Hack's Chemical Dictionary", McGraw-Hill Book Company 1969, Fourth Edition, page 27.

EXAMINER

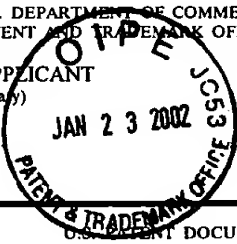
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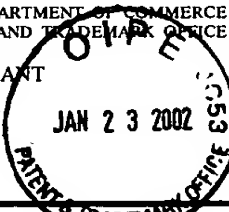


*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
JK	AA	4,474,975	10/84	Clemons et al.	556	410
JK	AB	5,962,581	10/99	Hayase et al.	524	588
JK	AC	5,677,015	10/97	Hasegawa	427	576
JK	AD	5,783,493	7/98	Yeh et al.	438	118
JK	AE	5,807,660	9/98	Lin et al.	430	313
JK	AF	4,833,096	5/89	Huang et al.	438	201
JK	AG	5,405,489	4/95	Kim et al.	438	698
JK	AH	5,470,772	11/95	Woo	438	588
JK	AI	5,652,187	7/97	Kim et al.	438	760
JK	AJ	5,656,337	8/97	Park et al.	427	539
JK	AK	4,805,683	2/89	Magdo et al.	216	40
JK	AL	5,874,367	2/99	Dobson	438	787
JK	AM	5,858,880	1/99	Dobson et al.	438	758
JK	AN	5,219,613	6/93	Fabry et al.	438	758
JK	AO	5,270,267	12/93	Quellet	438	597
JK	AP	5,541,445	7/96	Quellet	438	761
JK	AQ	6,022,404	2/00	Ettlinger et al.	106	404
JK	AR	5,709,741	1/98	Akamatsu et al.	106	287.11
JK	AS	4,648,904	3/87	Depasquale et al.	106	2
JK	AT	4,158,717	6/79	Nelson	428	446
JK	AU	5,667,015	9/97	Harestad et al.	166	383
JK	AV	5,661,093	8/97	Ravi et al.	438	763
JK	AW	5,536,857	7/96	Narula et al.	556	10
JK	AX	4,695,859	9/87	Guha et al.	257	64

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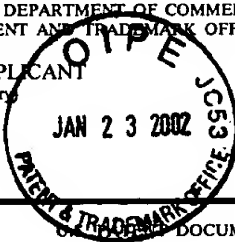
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gn	AA	5,061,509	10/91	Naito et al.	427	497	
gn	AB	4,600,671	7/86	Saitoh et al.	430	57.5	
gn	AC	5,753,320	5/98	Mikoshiba et al.	427	572	
gn	AD	5,356,515	10/94	Tahara et al.	438	715	
gn	AE	6,054,379	4/00	Yau et al.	438	623	
gn	AF	5,948,482	9/99	Brinker et al.	516	33	
gn	AG	5,800,877	9/98	Maeda et al.	427	535	
gn	AH	5,260,600	11/93	Harada	257	639	
gn	AI	4,992,306	2/91	Hochberg et al.	427	255.29	
gn	AJ	4,702,936	10/87	Maeda et al.	427	583	
gn	AK	4,863,755	9/89	Hess et al.	427	574	
gn	AL	5,234,869	8/93	Mikata et al.	438	793	
gn	AM	5,302,366	4/94	Schuetz et al.	423	346	
gn	AN	5,591,494	1/97	Sato et al.	427	579	
gn	AO	5,968,611	10/99	Kaloyeros et al.	427	579	
gn	AP	6,159,871	12/00	Loboda et al.	438	786	
gn	AQ	5,461,003	10/95	Havemann et al.	438	666	
gn	AR	6,124,641	9/00	Matsuura	257	759	
gn	AS	5,554,567	9/96	Wang	438	624	
gn	AT	6,028,015	2/00	Wang et al.	438	789	
gn	AU	5,744,399	4/98	Rostoker et al.	438	622	
gn	AV	5,883,014	3/99	Chen et al.	438	782	
gn	AW	6,017,779	1/00	Miyasaka	438	149	
gn	AX	6,156,674	12/00	Li et al.	438	780	

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gk	AA	6,140,151	10/00	Akram	438	113	
gk	AB	5,314,724	5/94	Tsukune et al.	427	489	
de	AC	5,376,591	12/94	Maeda et al.	438	761	
de	AD	5,817,549	10/98	Yamazaki et al.	438	166	
gk	AE	6,072,227	6/00	Yau et al.	257	642	
gk	AF	6,001,741	12/99	Alers	438	706	
gk	AG	5,786,039	7/98	Brouquet	427	578	
gk	AH	6,235,568	5/01	Murthy et al.	438	231	
gk	AI	6,187,694	2/01	Cheng et al.	438	142	
gk	AJ	5,750,442	5/98	Juengling	438	761	
gk	AK	6,114,255	9/00	Juengling	438	763	
gk	AL	6,238,976	5/01	Noble et al.	438	259	
gk	AM	6,008,121	12/99	Yang et al.	438	637	
gk	AN	5,140,390	8/92	Li et al.	257	350	
gk	AO	5,286,661	2/94	de Fresart et al.	438	343	
gk	AP	6,184,151	2/01	Adair et al.	438	743	
gk	AQ	6,225,217 B1	5/01	Usami et al.	438	637	
gk	AR	6,004,850	12/99	Lucas et al.	438	301	
gk	AS	6,140,677	10/00	Gardner et al.	257	327	
gk	AT	6,133,096	10/00	Su et al.	438	264	
gk	AU	6,136,636	10/00	Wu	438	231	
gk	AV	5,933,721	8/99	Hause et al.	438	217	
gk	AW	5,981,368	11/99	Gardner et al.	438	217	
gk	AX	6,159,804	12/00	Gardner et al.	438	265	
EXAMINER <i>J. De Rosa</i>				DATE CONSIDERED 5/20/02			
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<i>JK</i>	AA	6,130,168	10/00	Chu et al.	439	717	
<i>JK</i>	AB	6,235,591	5/01	Balasubramanian et al.	438	275	
<i>JK</i>	AC	6,198,144 B1	3/01	Pan et al.	257	42	
	AD						
	AE						
<i>JK</i>	AF	App. 09/146,843 (as filed and amended)		Li et al.			9/98
<i>JK</i>	AG	App. 09/234,233 (as filed and amended)		Li et al.			9/98
	AH						
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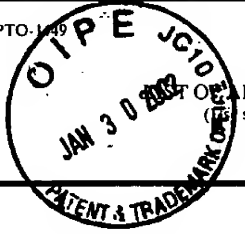
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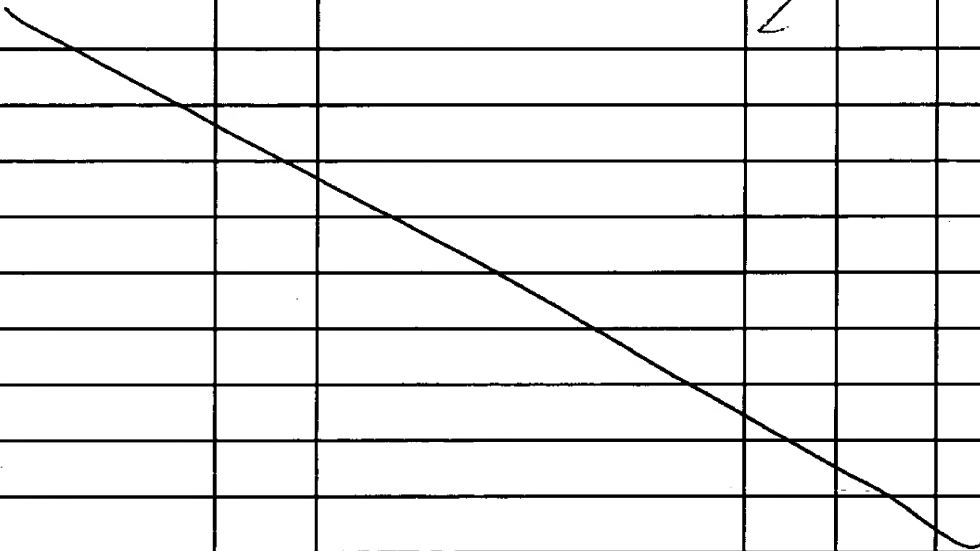
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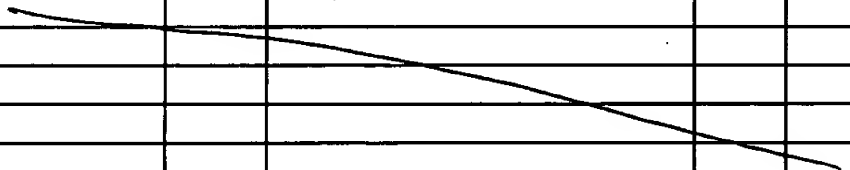
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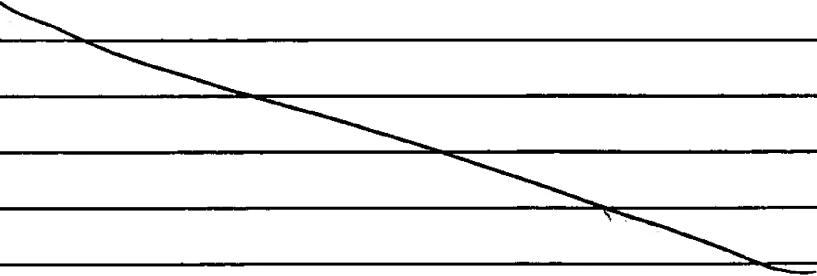
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→ OTHER REFERENCES

Form PTO-1499		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1427		SERIAL NO. 09/859,903	
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U.S. PATENT DOCUMENTS							
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	AA	6,268,282 B1	07/2001	Sandhu et al.	438	636	
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